PLASMA GRID IMPLANT SYSTEM FOR USE IN SOLAR CELL FABRICATIONS

ABSTRACT

A method of ion implantation comprising:

providing a plasma within a plasma region of a chamber; positively biasing a first grid plate, wherein the first grid plate comprises a plurality of apertures;

negatively biasing a second grid plate, wherein the second grid plate comprises a plurality of apertures;

flowing ions from the plasma in the plasma region through the apertures in the positively-biased first grid plate;

flowing at least a portion of the ions that flowed through the apertures in the positively-biased first grid plate through the apertures in the negatively-biased second grid plate; and implanting a substrate with at least a portion of the ions that flowed through the apertures in the negatively-biased second grid plate.

Fig. 1